Electromigration Test Structure Design

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Outline (Electromigration Test Structure)

- 1. Background of Electromigration
- 2. Critical Points of EM Test Structures
- 3. Design Electromigration Test Structure
- 4. Calculation and Analysis of EM Test Structure (with Excel and Simulation Tool)
- 5. Conclusion

1. Background of Electromigration (EM)

- ► Electromigration: Metal atoms swept out of position by high current density → failure (void/extrusion)
- Black's Law (Mean time to failure of a wire)

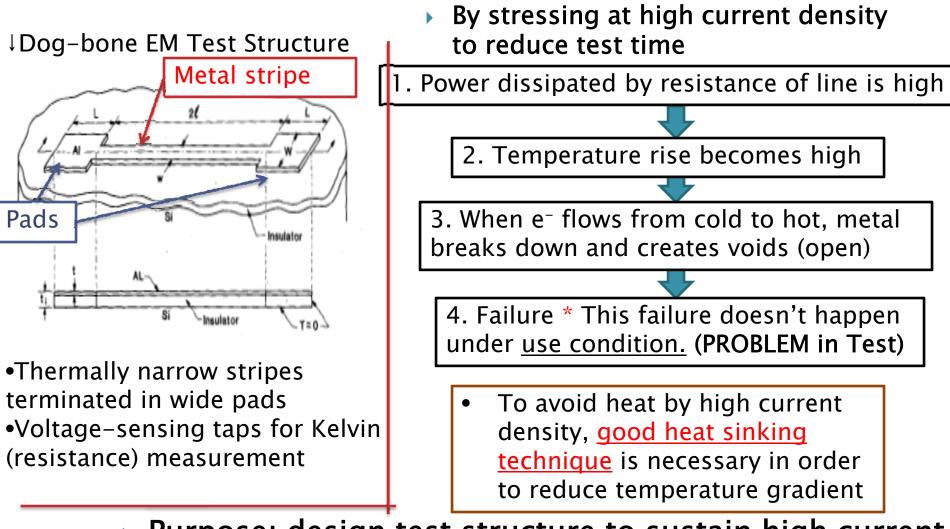
$$MTTF = \frac{A}{J^2} \exp(\frac{E_a}{kT})$$

Note: <u>Current density and</u> <u>temperature</u> are decaying factors J = current density T = film temperature A = cross-section of interconnect area Ea = activation energy (=0.7eV for Al) K = Boltzmann's constant

- With EM Test Structure, one can do ...
 - Find maximum current density that can be used in interconnects of technology
 - Expect device lifetime by stressing test structures at elevated temperature and high current density
 - Focus on J and T in EM Test Structure

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2. Electromigration Test Structure

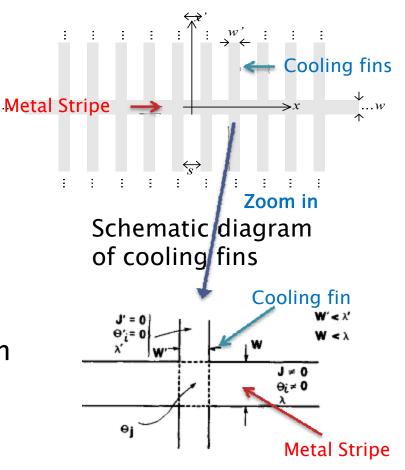


 Purpose: design test structure to sustain high current density but minimize temperature gradients

3. EM Test Structure (Dog-bone EM Structure with Cooling Fins)

- Solution to reduce temperature gradient is ...
 - Apply Cooling fins to stripe
- Want to prove this mathematically
 - 1. Calculate current density
 - 2. Calculate Temperature Gradient
 - 3. Estimate optimum space between cooling fins



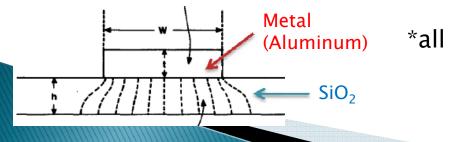


Schematic diagram of close-up test structure

3. Design EM Test Structure (Current Density)

- For accelerated test, we want as high current density as possible to <u>reduce testing time</u>
 - But, be careful with high temperature gradient.
- Limitations of EM test structure
 - 1.Thermal Runaway Current Density ($J_{max} = 10^{7}A/cm^{2}$)
 - 2. Temperature Gradient $d\Psi/dx$ as small as possible

Under use condition, $J_{use} = 2 \times 10^5 A/cm^2$ Under stress condition, $J_{stress} = 10^6 A/cm^2 < J_{max}$



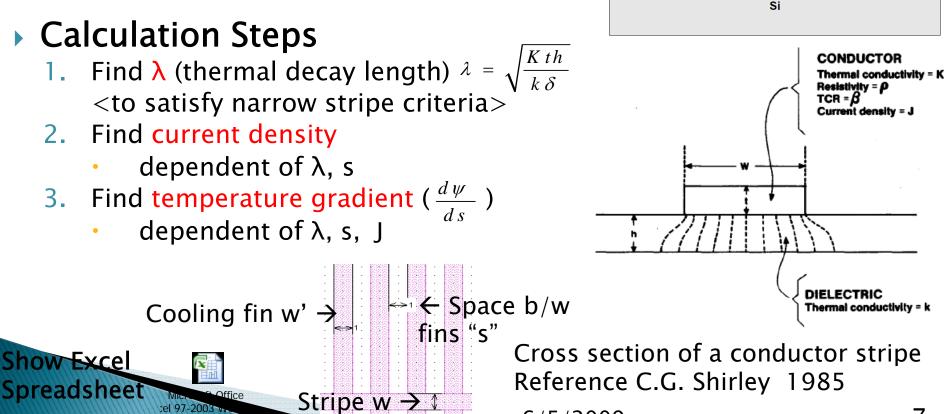
*all numbers here are approximated in t = h=1um technology

4. EM Test Structure Calculation

Assumptions

narrow stripe criteria (w, w' $<<\lambda$)

- w = w' = t = h = 1um
- This simplifies calculations a lot O



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SiO₂ (k)

4. Current Density vs Space b/w **Cooling fins Plot**

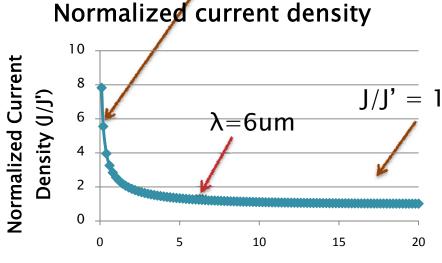
Normalized Current Density

$$\frac{J}{J_{s\to\infty}} = \sqrt{\frac{1 + \coth\left(\frac{s}{2\lambda}\right)}{2}}$$

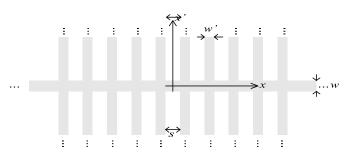
•coth(x) converges to 1 as $x \rightarrow \infty$

As space increases, current density goes down.

•Limited by Technology •DRC checks for min. space



Space between Cooling Fins (um)



4. Temperature Gradient vs Space b/w cooling fins plot

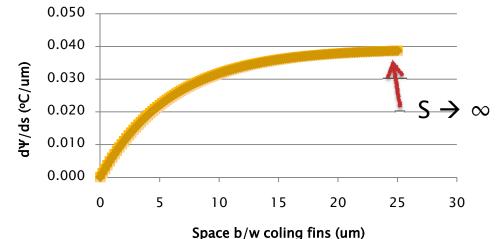
 Temperature Gradient Eqn. with generic "s"

$$\frac{d\psi}{ds} = \frac{J^2 \rho_s \lambda}{K \left[1 + \coth\left(\frac{s}{2\lambda}\right) \right]}$$

Temperature Gradient Eqn. as
s → ∞

 $\frac{d\psi}{ds} = \frac{J^2 \rho_s \lambda}{2K} = 0.0393^\circ C / um$

 As s increases, temperature gradient increases.

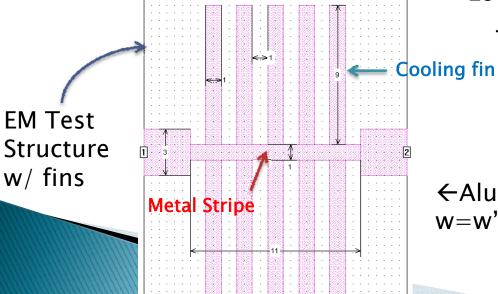


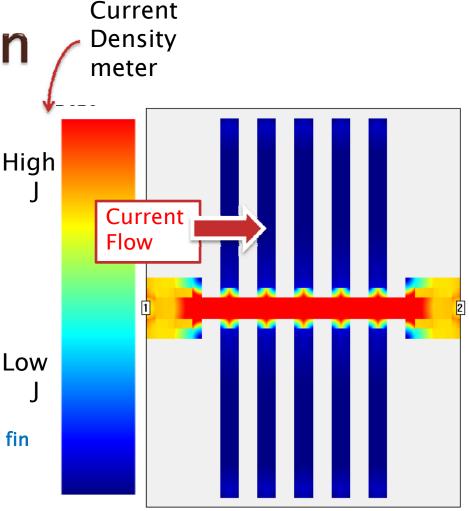
$$\begin{array}{l} J = 10^{6} A/cm^{2} \\ \rho_{s} = 2.82^{*}10^{-6}\Omega/cm \\ \lambda = 6.077um \\ K = 2.18 \ W/^{o}C \ cm \end{array}$$

Temperature Gradient (°C/um)

4. CD Simulation

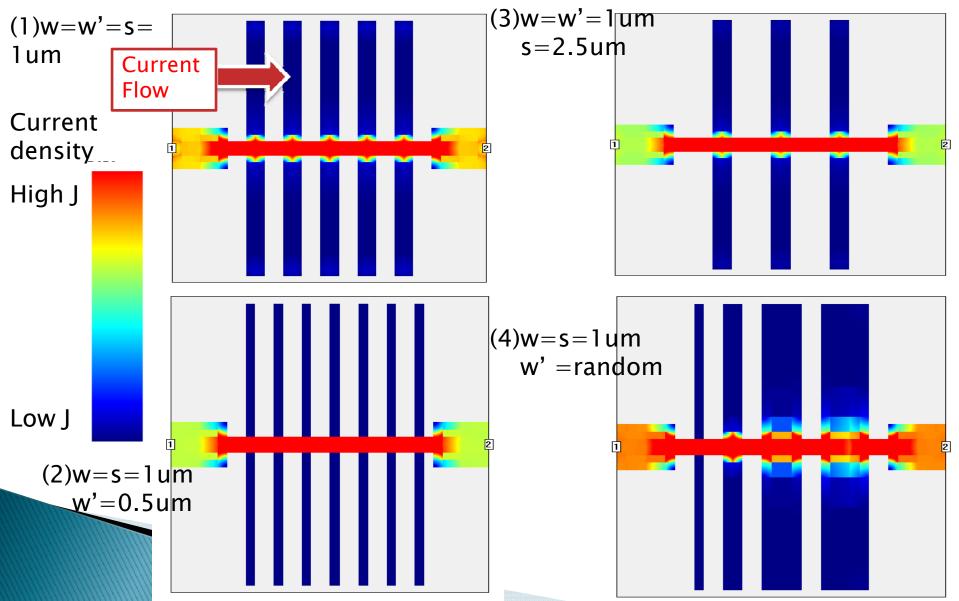
- Sonnet Lite Software (Limited Version) f = 1kHz High
- Want to see current density effect due to the space, width of cooling fins





←Aluminum Strip/Cooling fins/taps w=w'=s=1um diagram on Sonnet Lite

4. Current Density Simulation



5. Conclusion

- In accelerated test for EM, high current density is necessary to <u>reduce test time</u>.
- In order for a normal dog-bone EM test structure to have high current density, <u>temperature</u> <u>gradient</u> is a big problem for formation of voids.
- By adding <u>cooling fins</u>, temperature gradient is reduced (proved mathematically)
 - To get high current density and low temperature gradient, space needs to be as small as possible.
 - However, the size of spacing between cooling fins is limited by technology
 - pick s = { s_{min} (set by DRC) < s < λ = 6um } i.e. s = 1um

References

- C. G. Shirley, "<u>Steady-State Temperature</u> <u>Profiles in Narrow Thin-Film Conductors,</u>" J. Appl. Phys., Vol. 57, pp. 777–784, 1985
- J. R. Black, "Electromigration A Brief Survey and Some Recent Results," IEEE Transactions on Electron Devices Volume 16, Issue 4, Apr 1969 Page(s):338 – 347
- 3. ECE510 Applied Reliability Lectures



Questions?

